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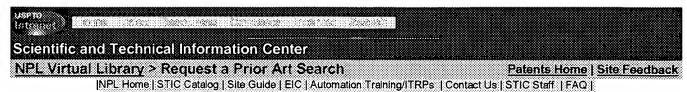
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Enter your Search Topic Information below:

Search claim 1:

1. An aqueous solution for micro-etching copper or a copper alloy comprising a main ingredient consisting of sulfuric acid and hydrogen peroxide, an assisting ingredient consisting of phenyltetrazole and a chloride ion source, and a benzene sulfonic acid.

[0015] In the above micro-etching composition, preferable examples of the phenyltetrazole are 1-phenyltetrazole or 5-phenyltetrazole.

[0017] In the above micro-etching composition, the chloride ion source is one or more compounds selected from the group consisting of sodium chloride, potassium chloride, ammonium chloride, and hydrochloric acid.

[0020] In the above micro-etching composition, the benzene sulfonic acid is one or more compounds selected from the group consisting of benzene sulfonic acid, toluene sulfonic acid, m-xylene sulfonic acid, phenol sulfonic acid, cresol sulfonic acid, sulfosalicylic acid, m-nitro benzene sulfonic acid, and p-aminobenzene sulfonic acid.

ABSTRACT:

A micro-etching composition and a printed circuit board fabricated by using the micro-etching composition are provided. The micro-etching composition, comprising a main ingredient consisting of v

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